

sub C2 *B2*

3. (Twice amended) A liquid crystal display device comprising a switching element formed on a substrate, a pixel electrode connected to said switching element, and a reflection layer,

wherein said pixel electrode is formed of a transparent conductive film, and
wherein said reflection layer formed of a dielectric multi-layer film is provided under said pixel electrode, and

wherein said pixel electrode has a thickness of 50.5 nm to 88.4 nm, and said thickness is satisfied with $\lambda/4$.

sub C3 *B3*

5. (Twice amended) A liquid crystal display device comprising a switching element formed on a substrate, a pixel electrode connected to said switching element, and a reflection layer,

wherein said switching element is connected to a capacitance,

wherein said capacitance comprising a common electrode formed of a transparent conductive film, a dielectric film formed on said common electrode, and said pixel electrode formed of a transparent conductive film formed on said dielectric film,

wherein said reflection layer formed of a dielectric multi-layer film is provided below said common electrode, and

wherein said pixel electrode has a thickness of 50.5 nm to 88.4 nm, and said thickness is satisfied with $\lambda/4$.

sub C4 *B4*

8. (Twice amended) A method of manufacturing a liquid crystal display device, comprising the steps of:

forming a switching element formed on a substrate;

a reflection layer formed of a dielectric multi-layer film above said switching element; and,

forming a pixel electrode formed of a transparent conductive film on said reflection layer,